


  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

  
In re the application of:

Tatsuo Enami, *et al.*

Serial No.: 09/518,639

Filed: 03/03/00

For: ArF EXCIMER LASER DEVICE  
SCANNING TYPE EXPOSURE DEVICE  
AND ULTRAVIOLET LASER DEVICE

Examiner: J. Zahn

Art Unit: 2828

**RESPONSE UNDER 37 C.F.R. § 1.111**

Honorable Commissioner  
of Patents and Trademarks  
Washington, D.C. 20231

April 25, 2002

Dear Sir:

The following remarks are submitted in response to the Official Action mailed January 30, 2002. The Official Action mailed on January 30, 2002, set forth a three-month period for response, making this response due on or before April 30, 2002.

Please amend the above-identified application as follows.

**IN THE SPECIFICATION:**

Please replace the paragraph beginning at page 5, line 12, with the following rewritten paragraph:

-- Therefore, the applicant for the present invention has proposed a technique to improve variations in the amount of light exposure due to

*Duplicate*  
*#9*  
RECEIVED  
MAY - 1 2002  
10 28 30 MAIL ROOM